

STRUCTURE COMPRISING TUNABLE ANTI-REFLECTIVE COATING AND METHOD OF FORMING THEREOF

ABSTRACT OF DISCLOSURE

An interconnect structure in back end of line (BEOL) applications comprising a tunable etch resistant anti-reflective (TERA) coating is described. The TERA coating can, for example, be incorporated within a single damascene structure, or a dual damascene structure. The TERA coating can serve as part of a lithographic mask for forming the interconnect structure, or it may serve as a hard mask, a chemical mechanical polishing (CMP) stop layer, or a sacrificial layer during CMP. ,